LA-UR-12-22379

Approved for public release; distribution is unlimited.

Title: Trapping of Implanted He at Cu/Nb Interfaces Measured by Neutron

Reflectometry

Author(s): Wang, Peng

Zhernenkov, Mikhail Kashinath, Abishek Demkowicz, Michael Baldwin, Jon K. Majewski, Jaroslaw

Intended for: ACNS2012, 2012-06-24/2012-06-29 (Washington DC, District Of Columbia,

United States)



Disclaimer:

Los Alamos National Laboratory, an affirmative action/equal opportunity employer,is operated by the Los Alamos National Security, LLC for the National NuclearSecurity Administration of the U.S. Department of Energy under contract DE-AC52-06NA25396. By approving this article, the publisher recognizes that the U.S. Government retains nonexclusive, royalty-free license to publish or reproduce the published form of this contribution, or to allow others to do so, for U.S. Government purposes. Los Alamos National Laboratory requests that the publisher identify this article as work performed under the auspices of the U.S. Departmentof Energy. Los Alamos National Laboratory strongly supports academic freedom and a researcher's right to publish; as an institution, however, the Laboratory does not endorse the viewpoint of a publication or guarantee its technical correctness.

Trapping of Implanted He at Cu/Nb Interfaces Measured by Neutron Reflectometry

Mikhail Zhernenkov, <u>Peng Wang</u>, Abishek Kashinath, Michael Demkowicz, Jon Baldwin, Jarek Majewski

LANSCE-LC











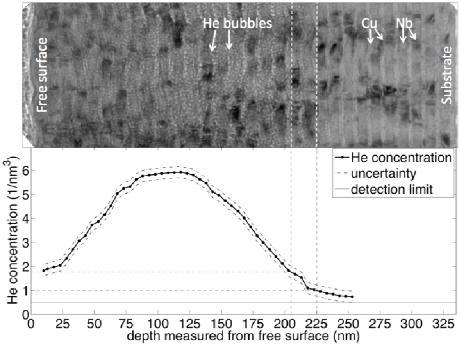
Motivation

In single crystalline metals, He is insoluble and precipitates into bubbles

In contrast, Cu-Nb multilayers show no evidence of bubble formation below a critical concentration

Questions

- How are the He atoms stored at the interface below the critical concentration?
- What is the C_{He} distribution?



[1] M. J. Demkowicz et al, Appl. Phys. Lett. 97 (2010) 161903

In Cu-Nb multilayers, the critical interface He concentration to resolve bubbles under the TEM is 8.5±2.5 atoms/nm² [1] (Multilayers implanted with 35 keV He³ with 10¹⁷/cm²).





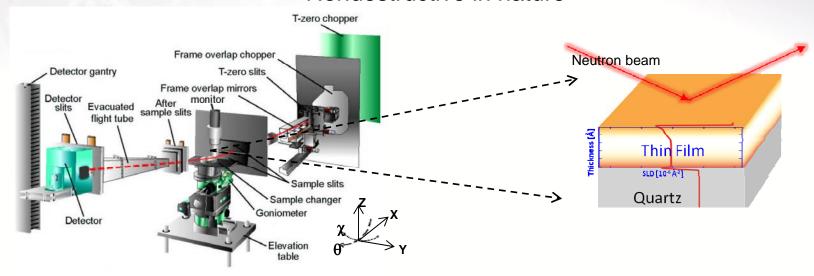




Why Neutron Reflectometry (NR)?



- Element sensitive
- Angstrom level depth resolution
- Nondestructive in nature



TEM: Cannot resolve He clusters smaller than 2 nm in diameter Elastic Recoil Detection (ERD): NOT enough depth resolution Nuclear Reaction Analysis (NRA): NOT enough depth resolution



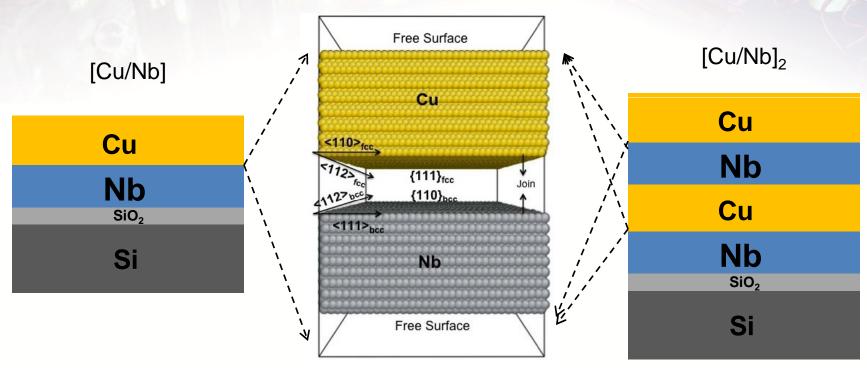






Strategies and Sample Preparation

Cu/Nb bi-layers: Magnetron Sputtering He Implantation: 20 KeV, 10¹⁷ ions/cm², < 2 μA/cm²



Construction of the Cu-Nb heterointerface.

Kurdjumov-Sachs (KS) orientation relationship

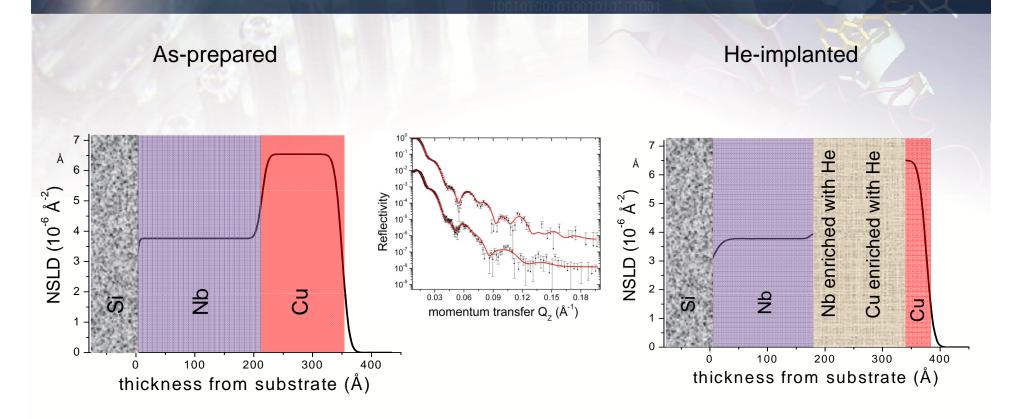








Sample [Cu/Nb]



- ■He trapped at Cu/Nb interface
- Cu is preferred









Results on Sample [Cu/Nb]

	Layer	Thickness (Å)	SLD (10 ⁻⁶ Å ⁻²)	Roughness (Å)	He (at. %)
As-prepared	Cu	136	6.54	14	
	Nb	211	3.76	11	
After Implantation	Cu	42	6.5	14.5	
	Cu + He	108	7.06	4	18
	Nb + He	53	3.95	15	12
	Nb	173	3.78	6	

- ■Significant broader interface
 -- 160 Å vs. 11Å
- ■Cu layer swelled 10%
- ■Nb layer swelled 7%

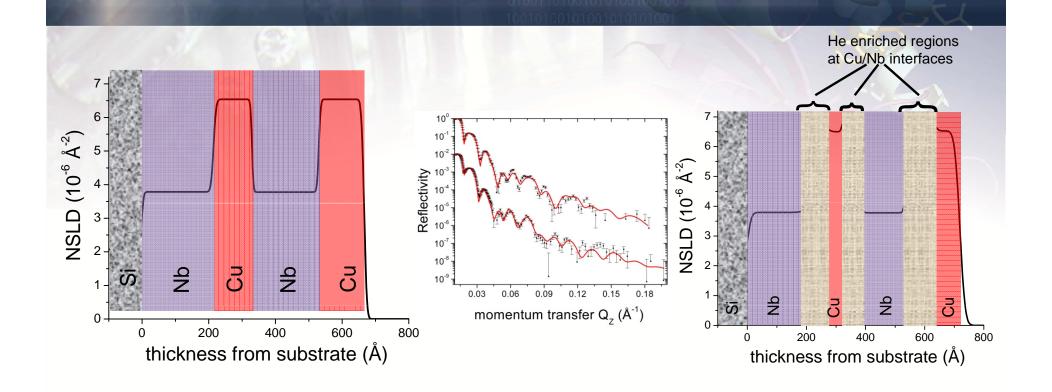








Sample [Cu/Nb]₂



- ■He trapped at Cu/Nb interface
- ■Cu is preferred









Results on Sample [Cu/Nb]₂

	Layer	Thickness (Å)	SLD (10 ⁻⁶ Å ⁻²)	Roughness (Å)	He (at. %)
As-prepared	Cu	136	6.54	9	
	Nb	201	3.78	6.4	
	Cu	115	6.54	5.3	
	Nb	216	3.78	8.8	
After Implantation	Cu	86	6.53	19.7	
	Cu + He	60	7.0	13	16
	Nb + He	45	4.2	10	20
	Nb	144	3.78	6	
	Nb + He	26	4.2	8.4	20
	Cu + He	40	6.86	19.8	12
	Cu	54	6.5	6	
	Cu + He	24	6.86	18.7	12
	Nb + He	60	3.95	6.4	10
	Nb	180	3.79	19.3	

Similar behavior as [Cu/Nb] sample; Interfacial region swells ~ 10 times



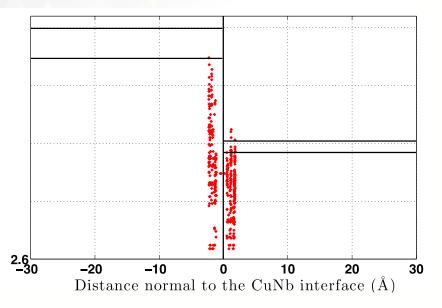




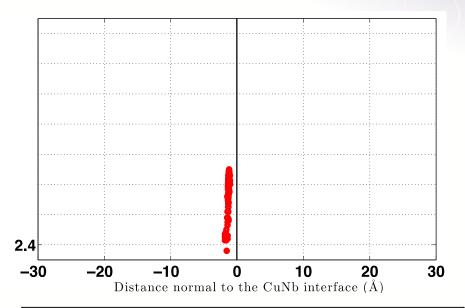


Atomistic modeling

- Based on Cu-Nb-He EAM Potential
- The formation energy of He defects is lower at the Cu-Nb interface compared to fcc Cu and bcc Nb
- Cu/Nb interface is preferred



Variation of the He interstitial energy in the direction normal to the Cu-Nb interface



Variation of the He substitutional energy in the direction normal to the Cu-Nb interface



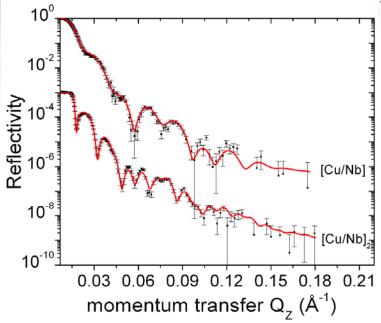






Control Sample

Cu/Nb bi-layers sputtered in He atmosphere (He 50% balanced with Ar)



	Layer	Thickness (Å)	SLD (10 ⁻⁶ Å ⁻²)	Roughness (Å)	He (at. %)
[Cu/Nb]	Cu	122	6.45	16.5	
	Nb	213	3.48	16	
[Cu/Nb] ₂	Cu	125	6.49	9	
	Nb	210	3.51	15	
	Cu	115	6.47	14	
	Nb	220	3.49	16	

Homogeneous He distribution

■ SLD_{Nb}: Reduced by 8%

■ SLD_{Cu}: Reduced by 1%

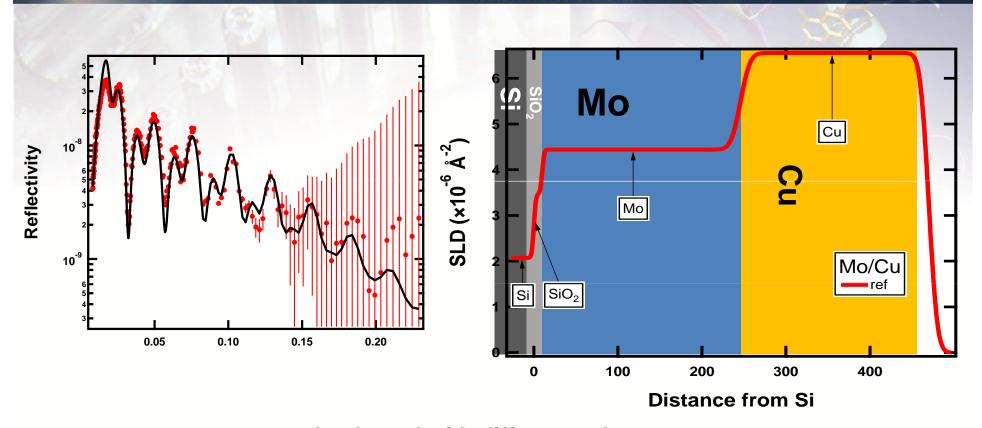


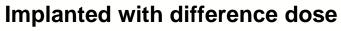






Cu/Mo Sample







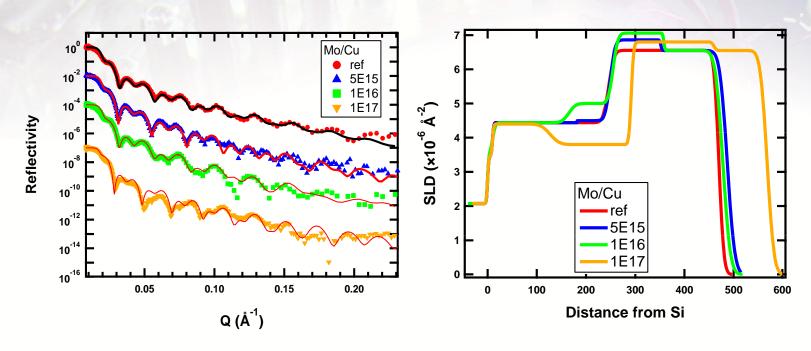






Cu/Mo Sample

Dependence on Implantation Fluence



- Implantation Fluence has effect on the He trapping behavior
- Critical concentration can be determined









Conclusion

- He is trapped at Cu/Nb , Cu/Mo interfaces.
- He is trapped interstitially
- The interface swells ~ 10 times
- The layered structure retains despite the swell of interfaces.

Future work

- Cu/V system
- Annealing of the Implanted metal bi-layers
- ³He vs. ⁴He: Bigger cross section









